



**NIST Combinatorial Methods Center**  
*Polymers Division*  
*National Institute of Standards and Technology*  
[www.nist.gov/combi](http://www.nist.gov/combi)

# NCMC Facilities

## Self-guided Tours

The NIST Combinatorial Methods Center (NCMC) facilities have become a hub of high throughput experimental design and measurement. NIST scientists and engineers, as well as guest scientists from around the world, come to our laboratories to learn from our expert staff and use our often one-of-a kind equipment.

Our contributions include assistance with the preparation of gradient substrates and thin film libraries, development of new combinatorial and high throughput (C&HT) measurement techniques, and guidance in programming, automation and data management. In some cases, we participate in research on collaborative projects across NIST and with the members of our center.

The NCMC facilities remain a focal point for visitors from industry, academic institutions, and government agencies. We have also hosted high-profile tours for the American Association for the Advancement of Science (AAAS), the US Patent and Trademark Office (USPTO), the American Institute of Physics (AIP), the Office of Science and Technology Policy (OSTP), and Nobel Prize winner Richard Smalley.

Please ask us many questions. We are happy to discuss and show off our work and hope that your visit is both productive and enjoyable. Thank you for coming.



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# Ask Our Experts

## FLOOR PLAN KEY

- 1. Surface-initiated library synthesis**  
- Heqing Huang (A206)
- 2. Epoxy formulation and dispensing**  
- Jae Hyun Kim (A208)
- 3. nScript deposition system**  
- Chris Stafford (A210)
- 4. Mapping thickness gradients via interferometry and ellipsometry**  
- Kirsten Genson (B209)
- 5. Surface energy gradients**  
- Chang Xu (B207)
- 6. Small angle light scattering**  
- Kirt Page (A212)
- 7. On-chip interfacial tensiometry**  
- Steve Hudson (A214)
- 8. Spectroscopy in fluidic devices & channels**  
- Susan Barnes (B215)
- 9. Multilens contact adhesion test**  
- Xuesong Hu (B217)
- 10. In-line particle sizing via DLS in channels**  
- Tom Chastek (B223)
- 11. Dimensional metrology via CD-SAXS**  
- Derek Ho (B317)
- 12. Combinatorial approaches to organic thin film transistors**  
- Leah Lucas (A330)

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